

<b>Notice of References Cited</b>		Application/Control No.	Applicant(s)/Patent Under Reexamination	
		10/544,783	TERASHIMA ET AL.	
		Examiner	Art Unit	Page 1 of 1
PAPE SENE		4135		

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Menachem Natan, "Anomalous first-phase formation in rapidly thermal annealed, thin-layered Si/Ni/Si films" August, 4th 1986, Applied Physics Letters, Vol. 49 Issue 5, pages 257-259.
	V	D. Mangelick et al., "Formation of Ni silicide from Ni(Au) films on (111)Si" April, 15th 1996, Journal of Applied Physics, Vol. 79 Issue 8, Pages 4078-4086.
	W	B. Bokhonov et al., "In-situ investigation of the formation of nickel silicides during interaction of single-crystalline and amorphous silicon with nickel" April, 26 <sup>th</sup> 2001, Journal of Alloys and Compounds, Vol. 319, Pages 187-1195.
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.